

**RECEIVED
CENTRAL FAX CENTER****APR 16 2007****IN THE UNITED STATES PATENT & TRADEMARK OFFICE**

Application No.: 10/520,366

Filed: 6 January 2005

By: Danziger, Manfred

For: Method and System for Processing

Carrier Materials by Heavy Ion Irradiation
and Subsequent Etching

Examiner: Dahimene, Mahmoud

Art Unit: 1765

Confirmation No.: 5933

P.O. Box 381516
Cambridge MA 02238-1516
23 November 2006Hon.
Commissioner for Patents
P.O. Box 1450
Alexandria VA 22313-1450**Amendment**

Sir:

This is in response to the Official Action dated 24 August 2006.

With a view to putting the specification into a format believed to comply with current American patent prosecution standards and to edit its English idiom, Applicant courteously requests entry of the following amendment.

In the Specification:

Page 1, between lines 6 and 7 insert: --BACKGROUND OF THE INVENTION.

1. Field of the Invention.--

line 8: after "and" insert --to-- and after "processing" insert --a--;

between lines 12 and 13: insert --2. The Prior Art.;

line 23: change "be" to --by--;

page 2, line 14: change "foils" to --films--;

line 15: change "foil" to --film--;

line 17: change "foil" to --film--;

line 18: change "during" to --over--;

line 20: change "the" to --their--;

line 21: change "plugged up" to --congested--;

line23: change "achieved again" to --restored--;